

10201707368T

Text of the abstract

Disclosed herein in an anti-reflective glass structure comprising a glass substrate and a multilayer of alternating dielectric layers having high refractive index and low refractive index, wherein the first dielectric layer over the glass substrate has high refractive index. In a preferred embodiment, said dielectric layers are prepared by using magnetron sputtering. Furthermore, the high refractive index dielectric layer is selected from the group consisting of NbO, NbO₂, Nb₂O₅, ZrO, Zr₂O₃, TiO and TiO₂, wherein said dielectric layer has a refractive index of between and including 2.0 and 2.3. In addition, the low refractive index dielectric layer is formed from SiO₂.